
HOLISTIC TRANSFORMATION IN HIGH VOLUME MANUFACTURING OF DATA CENTER TRANSCEIVERS

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Acknowledgement

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*MASSTART project is an initiative of the **Photonics Public Private Partnership**. www.photonics21.org*



PHOTONICS PUBLIC PRIVATE PARTNERSHIP

Empowering Photonic Interconnects for Data Center and Next Generation Computing

Fraunhofer IZM:

- System concept and design
- Photonic and RF component design
- Signal integrity and board design
- Silicon photonics interposer
- Through silicon via (TSV)
- 3D integration
- Flip chip assembly
- Co-packaging
- System evaluation
- Benchmarking



PhoxTroT
Optical Interconnections & 3D Integration Technologies

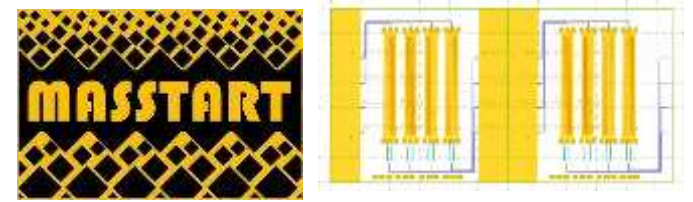
480 Gb/s
12 ch. Tx/Rx

1.6 Tb/s
8x8 switching matrix

1.6 Tb/s
16-ch. WDM



L3MATRIX
LARGE, LOW POWER AND LOW COST DATA CENTRES
Co-Package Technology Platform



Transceivers for Tb/s inter and intra Data Centers applications



Empowering Photonic Interconnects for Data Center, Next Generation Computing, Next Generation Networks

1

PROMETHEUS

Programmable photonics enabling ultra-fast spiking and quantum neural networks

2

OCTAPUS

Optical circuit switched time sensitive network architecture for high-speed passive optical networks and next generation ultra-dynamic and reconfigurable central office environments

3

ADOPTION

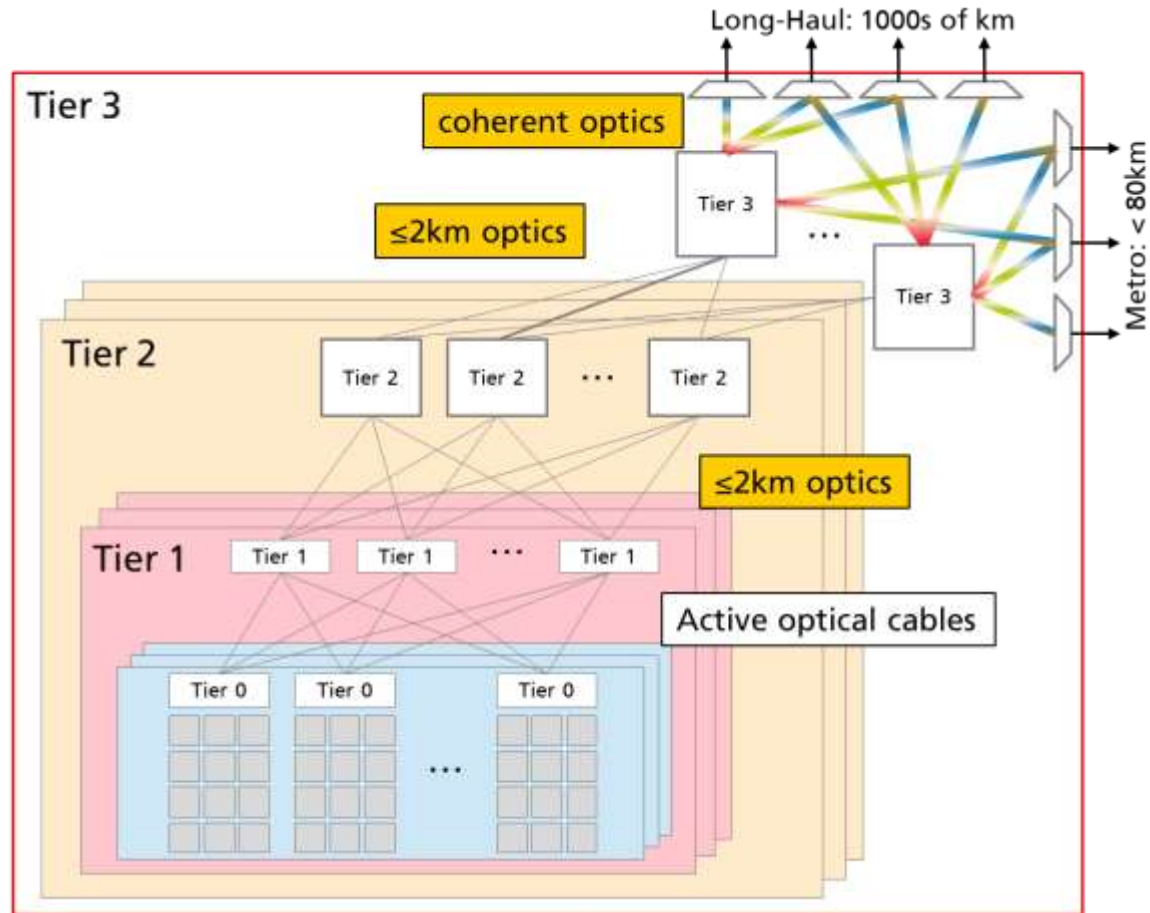
Advance co-packaged optics enabling high-efficiency cloud computing

4

ALLEGRO

Agile ultra low energy secure networks

Data Center Architecture Metrics



Volume

Complexity

Standardization

Cost

Si Photonics

Tier 0 switches service a rack

Tier 1 switches service a „row“ (of racks)

Tier 2 switches service a „Co-location“

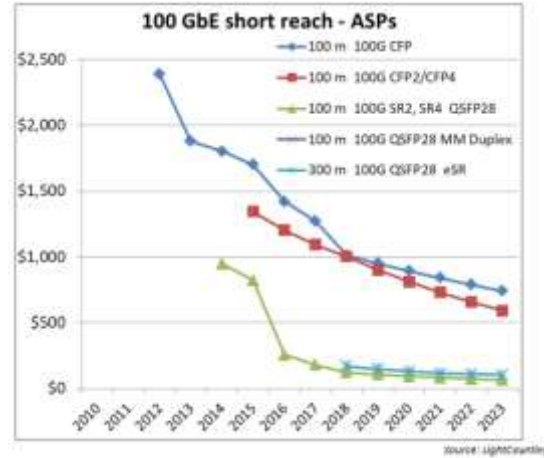
Tier 3 switches service a data-center

- Interface to long-haul network
- Also interface to metro network

Data Center Transceiver Metrics

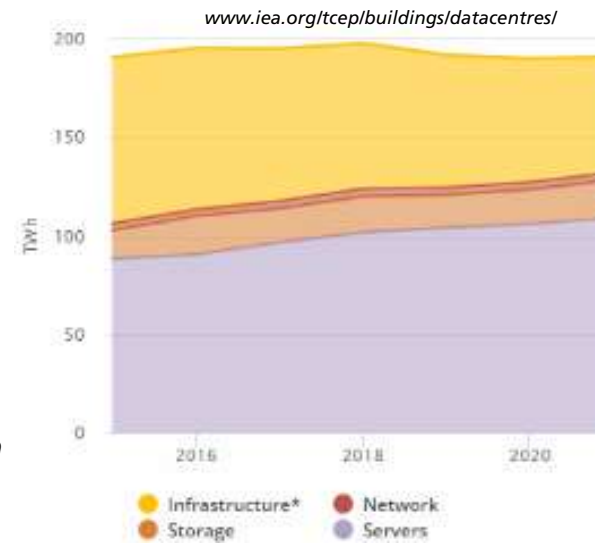
Lower Cost

Sub \$1/G is an industry-wide goal



Lower Power

Optical interconnects power consumption amounts to ~2% of the total DC power; however, within a rack they are critical.



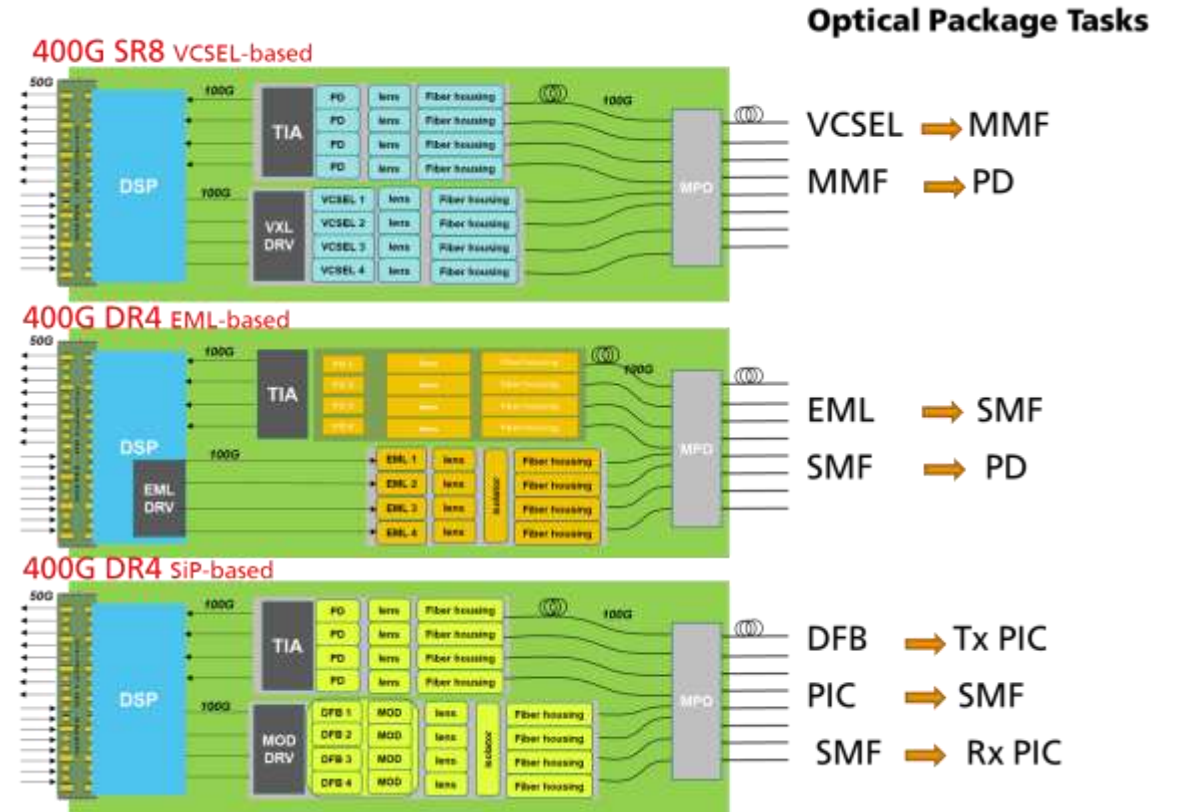
Higher Reliability

Transceiver failures in the DC requires constant maintenance



Cost, Power and Reliability Optimization Requirements

- Design for high volume manufacturing: passive or fully-automated
- Design for reduced BOM
- Eliminate labor-intensive alignment steps (COGS)
- Support extended reach, high temperature with single design
- Support all data rates with a single optical design



MASSTART



- System providers
- Photonic Assembly & Testing
- Design House & Technology consultancy
- Technology providers

High-Power DFB Lasers based on Al-free MQW

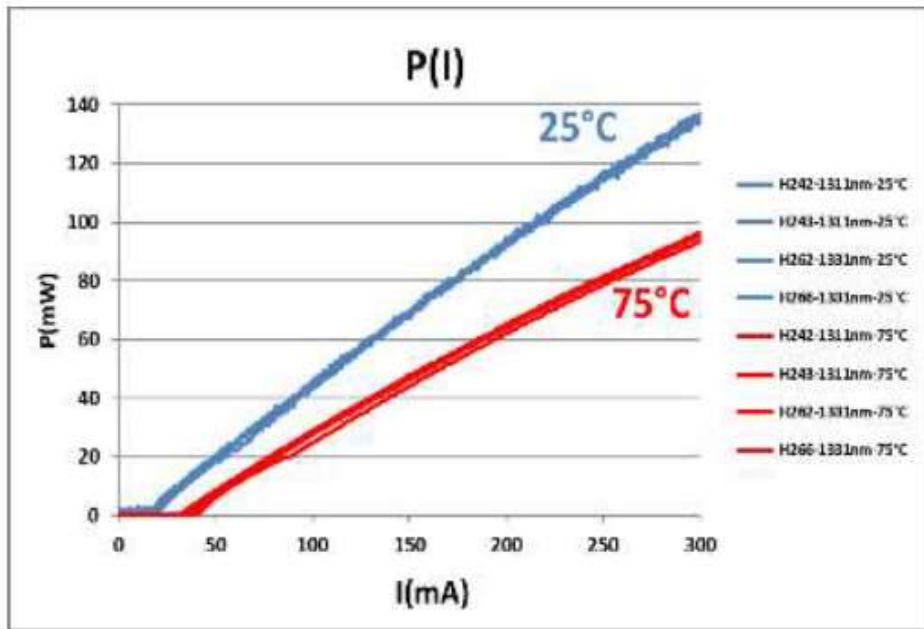


WAFT : Pitch and Mode Adaptation

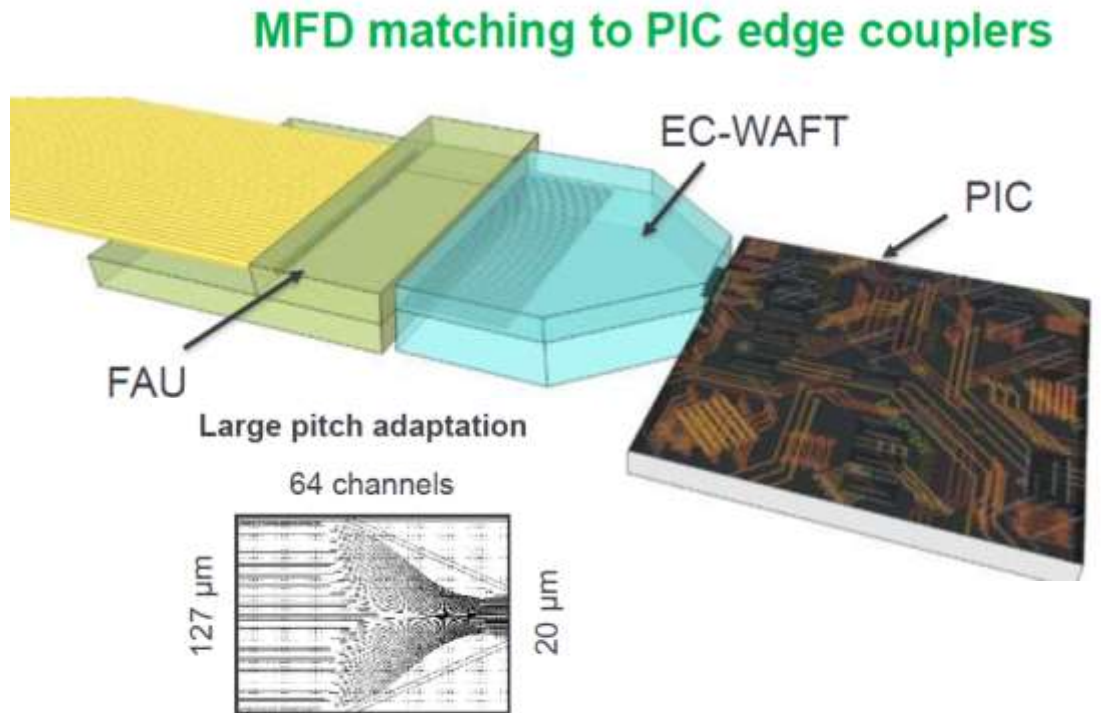
- Uncooled DFB with low I_{th} and high P_{out}
- Compatible with SiBH technology

- Insertion loss (incl. fiber) <math><0.7\text{dB}</math>
- MFD $4 \times 3\mu\text{m}$ ($1/e^2$), pitch $>20\mu\text{m}$
- SM and PM compatible

New generation of HPDFB



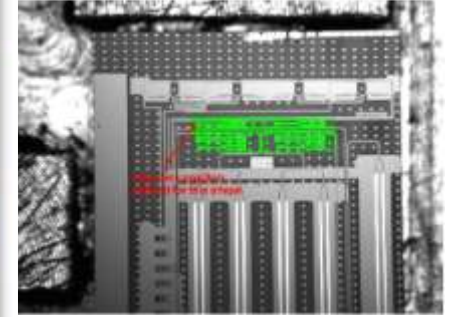
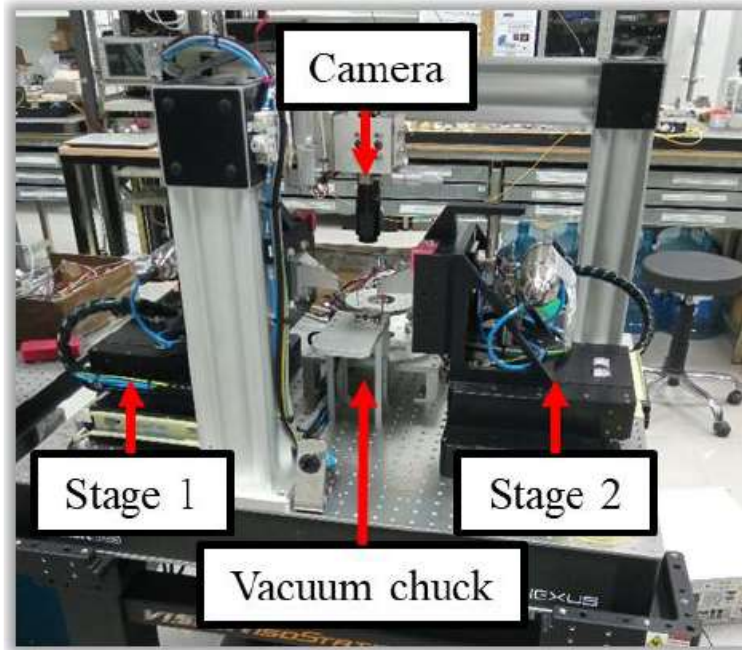
The output power is improved by 25% at high temperature operation



Inter- and Intra- Data Center Design Challenges up to 1.6 Tb/s

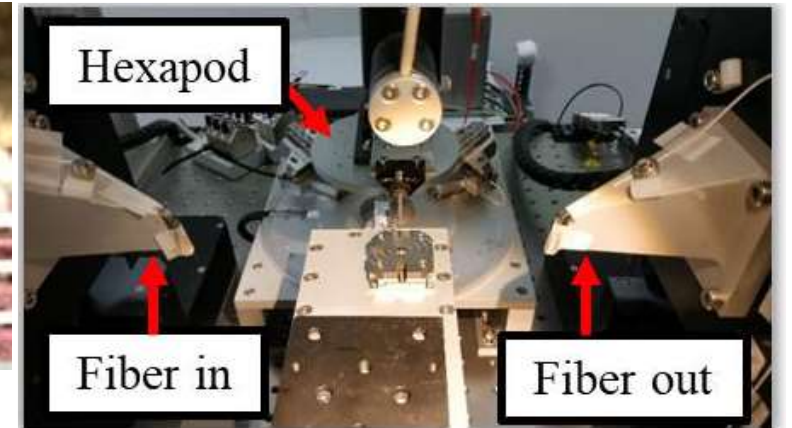
- Multiple technologies: Si-Photonics, III-V, Glass
- PDK for separate technology mapped layers
- Multiple IP Building Blocks
- Complex routing and design rules
- New generation of assembly, coupling and packaging approach
- Create packaging rules, packaging templates, import fiducial markers

Automated Die Tester Platform

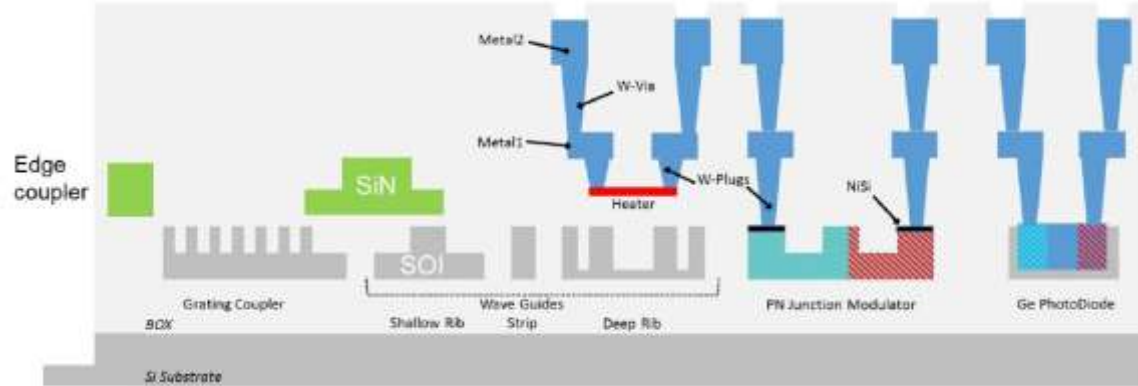


```
# import PDK
# import IP BBs
# import Fiducials

import nazca
import leti
import teem
import izm
import apt
import bright
import ficonTEC
import dust
```



Silicon Photonics Technology KPIs and Device Libraries



- **Advanced 300mm Si platform**
- Substrates : SOI 310nm and 220nm
- Si patterning with immersion lithography
- 60nm smallest feature size
- > 200 steps ; 24 litho levels
- 40 metro/control steps
- Low optical losses: 0.6-2 dB/cm
- **Versatility:** combine building blocks

Ge photodiode

Responsivity	0.7 A/W
Dark current @ -2V	5 nA
BW @ -2V	> 35GHz

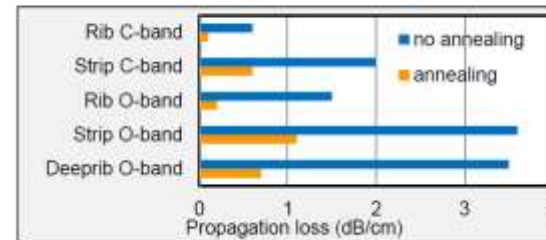
MZ modulators

$V_{\pi L}$ @ -2V (V.cm)	1.5
Losses (dB/cm)	7
BW@-6dB (GHz)	25

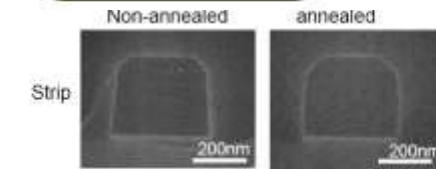
Low-loss Si waveguides:

- Roughness reduction with smoothing annealing (H2 850°C)
- Record low propagation losses in Si <1dB/cm
- No shape modification: no impact on other devices
- No impact on modulator efficiency

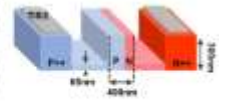
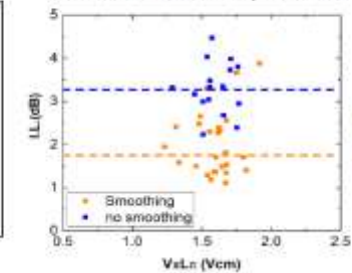
Strip WG @1310nm	1.1dB/cm
Strip WG @1550nm	0.7dB/cm




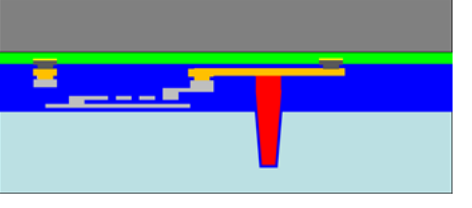
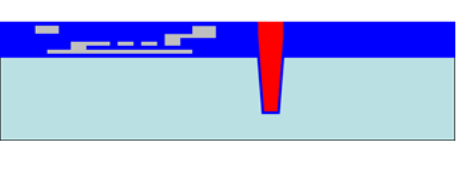
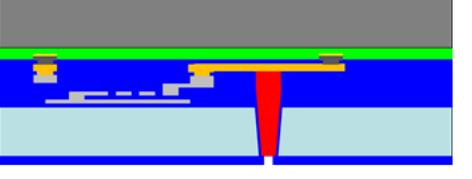
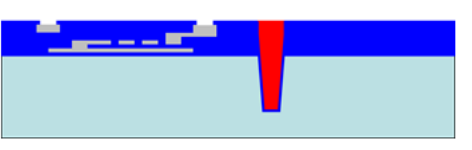
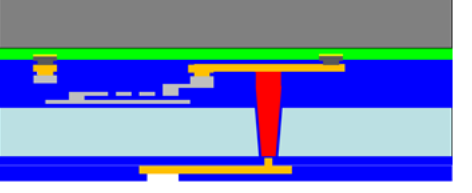
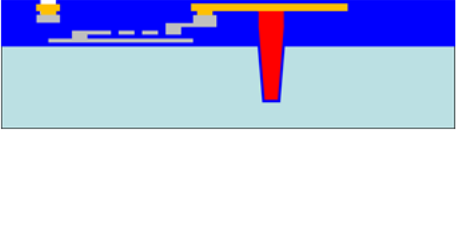
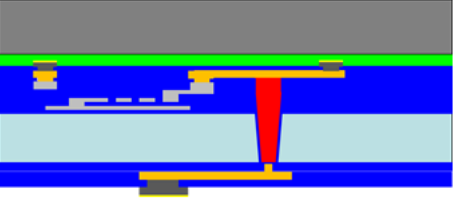
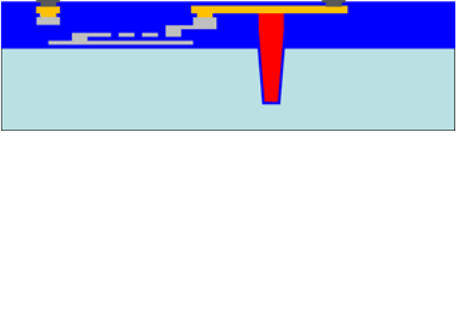
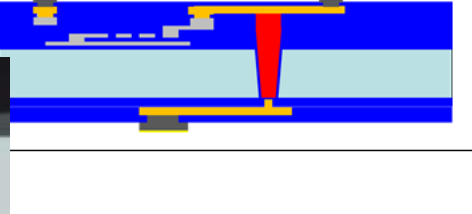
Q. Wilmar et al., Journal of Lightwave Technology (2021)



PN junction efficiency preserved
dBs of insertion loss improvement



Front and Back Side Processes for TSV, RDL and IO formation

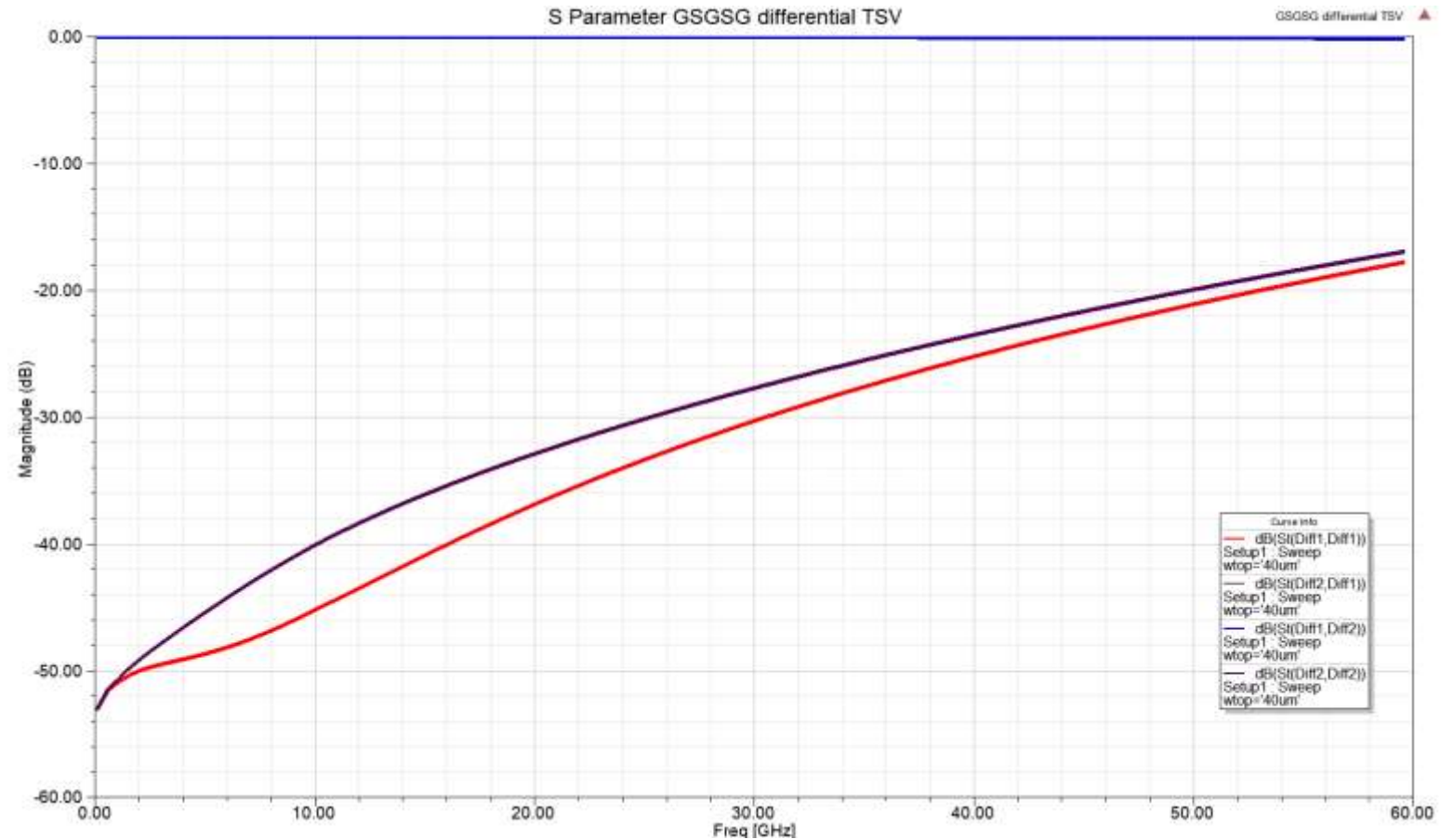
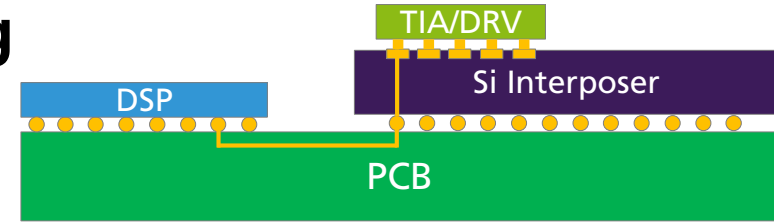
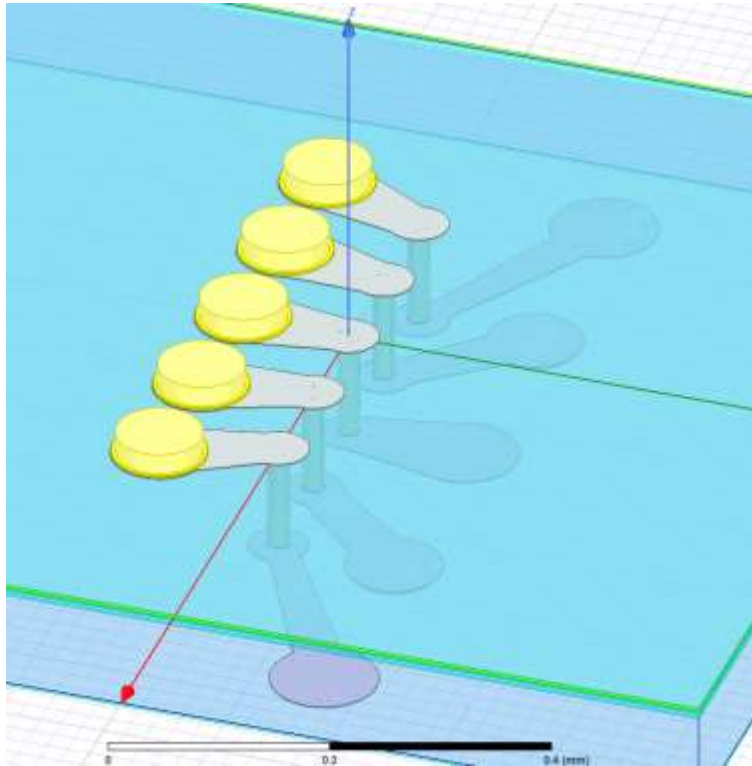
<p>1. Original wafer condition</p> <ul style="list-style-type: none"> Original IO pads opened keep out zones in FEOL and BEOL (red circle) 		<p>7. Temporary carrier bonding</p>	
<p>2. TSV process</p> <p>(Litho mask required-->layer 10 in current TRX8 layout)</p> <ul style="list-style-type: none"> original IOs pads are covered with passivation layer after TSV process 		<p>8. Back grinding / TSV reveal</p> <p>9. Back side passivation (1µm CVD Oxide / Nitride)</p> <p>(Litho mask required-->layer 9 in TRX8 layout)</p>	
<p>3. Passivation opening over original IO pads</p> <p>(Litho mask required-->layer 8 in current TRX8 layout)</p>		<p>10. Back side RDL (1µm Al)</p> <p>(Litho mask required-->layer 21 in TRX8 layout)</p> <p>11. RDL passivation (1µm CVD Oxide / Nitride)</p> <p>(Litho mask required-->not foreseen in TRX8 layout)</p>	
<p>4. Front side RDL formation (1µm Al)</p> <p>(Litho mask required-->layer 11 in current TRX8 layout)</p> <p>5. RDL passivation (1µm CVD Oxide / Nitride)</p> <p>(Litho mask required-->not foreseen in TRX8 layout)</p>		<p>12. Back side pad metallization deposited</p> <p>(Litho mask required-->not foreseen in TRX8 layout)</p>	
<p>6. Front side pad metallization</p> <p>(Litho mask required-->not foreseen in TRX8 layout)</p> <ul style="list-style-type: none"> original IOs can be covered with pad metallization pad metallization to be located at all positions where passivation is opened pad formation on top of TSVs not allowed 		<p>13. Temporary carrier de-bonding</p>	



GSGSG TSV Application Scenario / Co-Packaging

Required to connect:

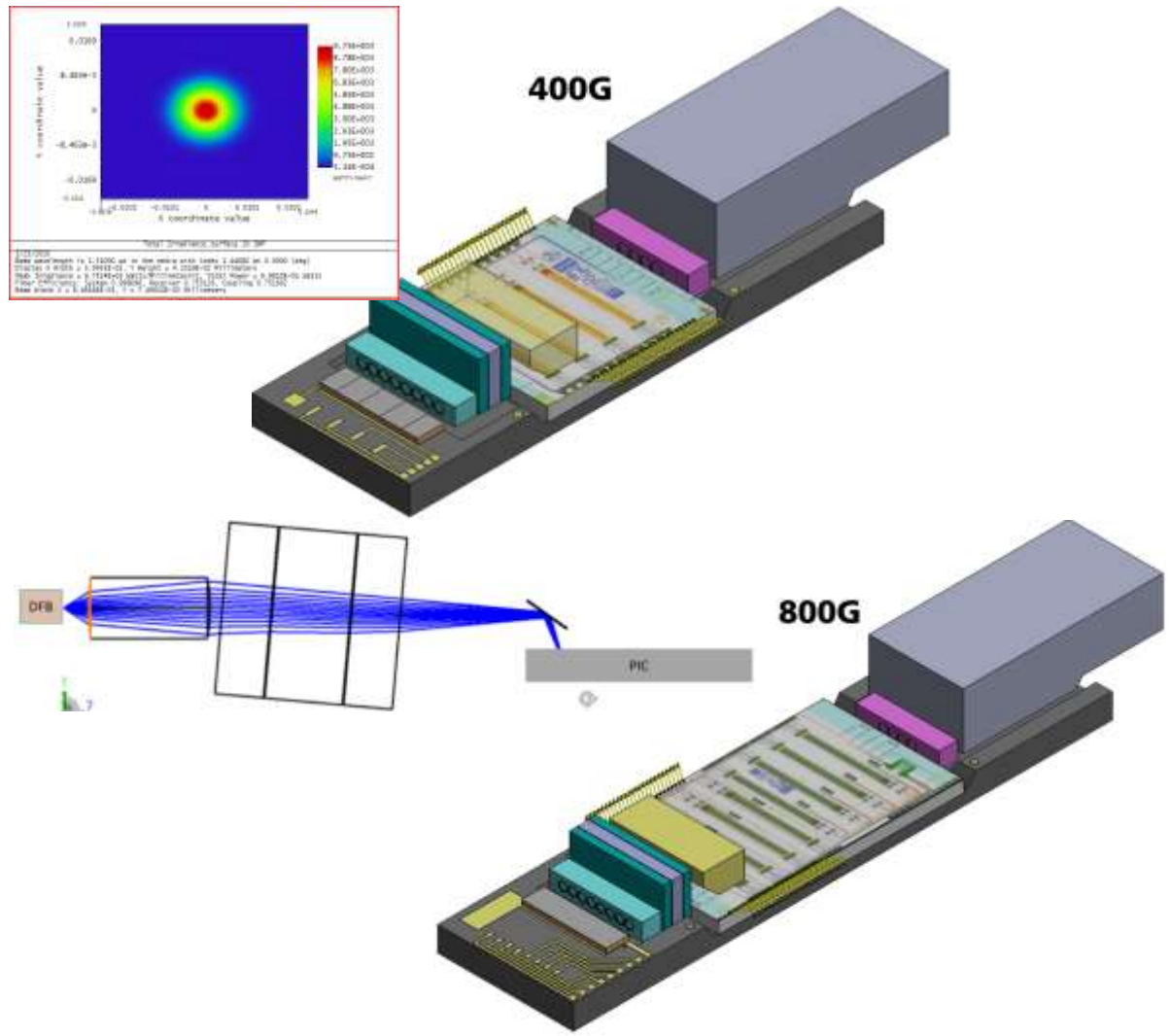
- Driver/TIA chips assembled on top of the Interposer
- DSP chip assembled on the PCB



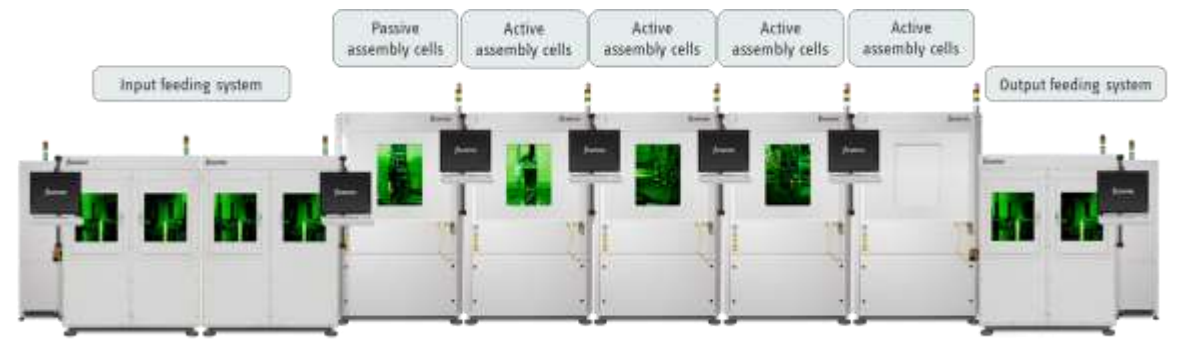
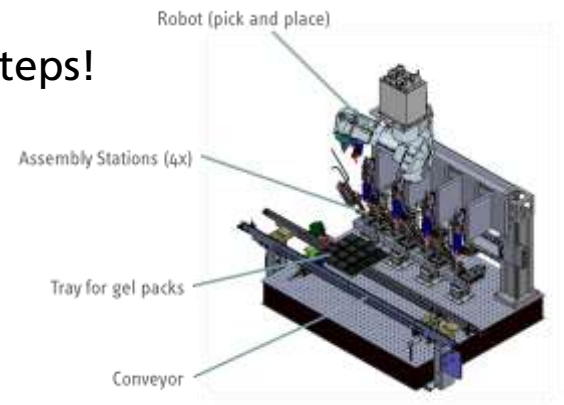


Module Coupling

Mass manufacturing line for DC interconnects (possible layout)

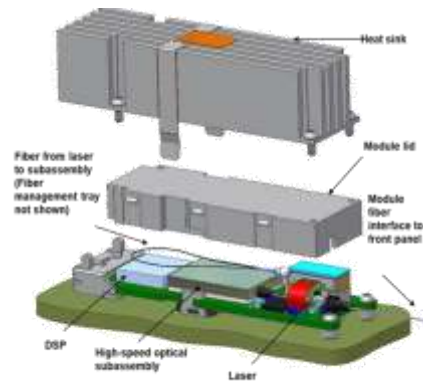


- Final cost defined by
- Machine costs
- Footprint / Clean room area
- Throughput of all assembly steps!



Coherent transceiver with 600Gb/s capacity (DP-64QAM)

- A tunable single-wavelength
- Following the DP-64QAM modulation format on 64Gbaud/s line rate
- Engine for pluggables and line-cards
- Modulator, receiver, driver, TIA and control IC
- Solder reflow compatible
- BGA contacts for highest RF-performance
- OIF standard, 15 x 22.5 x 3.6mm footprint



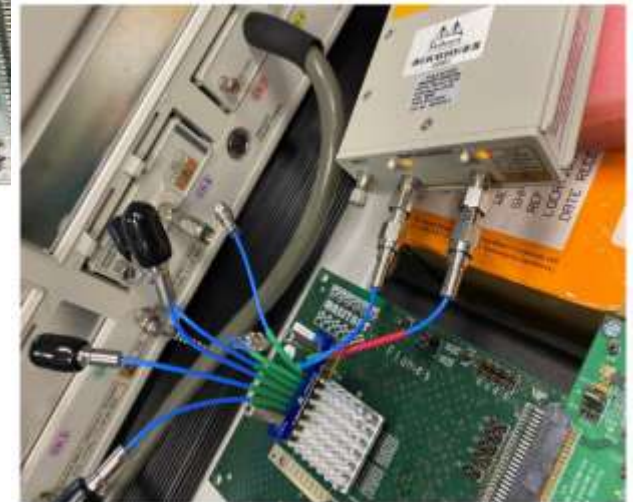
Source: ADVA

4-Channel PSM4 Module in QSFP-DD Format with 400G Aggregate Bit Rate

Rosenberger Based Prototype



Ardent Based Prototype



How to enable mass-manufacturing of datacom photonics products?

- Automated manufacturing
 - Optical transceivers transfer rates > 1Tb/s
 - Competitive costs according to the interconnection distance
 - Proven designs
 - Chip manufacturing (photonic/electronic)
 - Integration & Packaging
 - Testing
 - Demonstration in a real environment
 - Standardization
- PIC-based optical transceivers with transfer rates above 1Tb/s enabling massive deployment in datacenter environments (<1€/Gbps between racks and <0.1€/Gbps inside racks)

→ **Ecosystem and improved cross fertilization
between photonics and other technology areas**

8th International Symposium for Optical Interconnect in Data Centres

Wed., 21. September 2022,

ECOC 2022, Basel, Switzerland

Applause ECSEL Project

Heterogenous Integration Summer School

29.-30. September 2022,

ESREF 2022, Berlin, Germany



MASSTART Project

19.-21. September 2022,

Berlin-Brandenburg Pavilion (booth #411)

ECOC Exhibition 2022, Basel, Switzerland



We are constantly looking for new talents!

Optical - wireless networks

Photonic neural networks

Transmit and Receive Module Coupling

